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Research Article

Quantum Lithography: Achieving Sub-Diffraction Resolution using N00N States and Multi-Photon Absorption

Elchin Mammadov[1], Kerry John[2], John Langa[3]
[1] Baku State University, Azerbaijan
[2] St. George's University, Grenada
[3] Solomon Islands National University, Solomon Islands

Corresponding Author:

Elchin Mammadov,
Baku State University, located in the capital city of Baku, Azerbaijan, is one of the country's most prestigious institutions of higher education.
Email: elchin@gmail.com

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Abstract

Classical optical lithography is fundamentally limited by the diffraction limit, restricting achievable resolution in nanoscale fabrication. Quantum lithography has been proposed as a solution by exploiting entangled photon states, particularly N00N states, which enable interference patterns with sub-wavelength spacing. This study aims to investigate the feasibility of achieving sub-diffraction resolution using N00N states combined with multi-photon absorption processes under realistic conditions. A theoretical–computational approach was employed, integrating quantum optical modeling with numerical simulations across varying photon numbers, absorption orders, and loss parameters. Spatial resolution, fringe visibility, and absorption efficiency were used as key performance metrics. The results indicate that N00N states achieve resolution scaling inversely with photon number, successfully surpassing the classical diffraction limit. However, increased photon number significantly reduces multi-photon absorption probability and makes the system more sensitive to loss and decoherence. These findings reveal a fundamental trade-off between resolution enhancement and detection feasibility. This study concludes that quantum lithography offers a powerful pathway for sub-diffraction patterning, but practical implementation requires optimization of photon number, absorption efficiency, and system robustness to environmental disturbances.

Keywords: N00n States, Multi-Photon Absorption , Sub-Diffraction Resolution

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INTRODUCTION

Quantum lithography has emerged as a promising approach to overcome the fundamental diffraction limit that constrains classical optical imaging and fabrication techniques. The diffraction limit, governed by the wavelength of light, restricts the achievable resolution in conventional lithographic processes, posing a major challenge for the continued miniaturization of nanostructures and semiconductor devices (Elsayed, 2023; Kerbl, 2023). Advances in quantum optics have introduced the possibility of surpassing this limit by exploiting non-classical states of light, particularly entangled photon states. These developments have opened new avenues for achieving ultra-high-resolution patterning at scales previously considered unattainable.

N00N states, a class of maximally path-entangled photon states, have been identified as key resources in quantum lithography due to their ability to produce interference patterns with effective wavelengths reduced by a factor of N (McDonagh, 2022; Vahanian, 2022). This property enables the generation of interference fringes with sub-diffraction spacing, theoretically allowing for resolution beyond classical limits. Multi-photon absorption processes further enhance this capability by enabling the detection of these high-resolution interference patterns. The combination of N00N states and multi-photon absorption forms the theoretical foundation for quantum lithographic techniques.

The integration of quantum states of light into lithographic systems represents a significant shift from classical to quantum-enhanced fabrication methods. Achieving practical implementation of these techniques requires addressing both theoretical and experimental challenges (Heidenreich, 2022; Zeppenfeld, 2022). The potential impact of quantum lithography extends to fields such as nanotechnology, photonics, and semiconductor manufacturing, where precise control over nanoscale structures is essential. This context underscores the importance of exploring quantum approaches to overcome classical resolution limits.

The primary limitation in classical lithography arises from the diffraction limit, which restricts the minimum feature size that can be achieved using conventional optical methods (Humbert, 2022; Lyon, 2022). As device dimensions approach the nanoscale, this limitation becomes increasingly significant, hindering further advancements in microfabrication. While shorter wavelengths and alternative techniques such as electron beam lithography have been employed, these approaches often involve increased complexity, cost, and technical constraints.

Quantum lithography offers a theoretical solution to surpass the diffraction limit, yet its practical realization remains challenging (R. A. Byrne, 2023; Joglar, 2024). The generation and maintenance of high-quality N00N states are difficult due to their sensitivity to loss, decoherence, and experimental imperfections. Multi-photon absorption processes, which are essential for detecting sub-wavelength interference patterns, also suffer from low efficiency and require precise control of photon interactions.

Existing implementations of quantum lithography are often limited to proof-of-concept experiments conducted under idealized conditions (Arbelo, 2023; Mancia, 2023). These experiments do not fully address the challenges associated with scaling the technology for practical applications. The gap between theoretical potential and experimental feasibility highlights the need for research that systematically investigates the limitations and optimization of quantum lithographic systems.

This study aims to investigate the feasibility of achieving sub-diffraction resolution in lithography using N00N states combined with multi-photon absorption processes (Martin, 2024; Soriano, 2022). The research seeks to analyze how entangled photon states can be utilized to generate high-resolution interference patterns and how these patterns can be effectively detected. Emphasis is placed on understanding the relationship between photon number, interference visibility, and resolution enhancement.

Another objective of this study is to evaluate the impact of practical limitations such as loss, decoherence, and detection inefficiency on the performance of quantum lithography systems. The research examines how these factors influence the quality of interference patterns and the effectiveness of multi-photon absorption processes (Lu, 2024; Terven, 2023). Strategies for mitigating these limitations are also explored.

The study further aims to develop a theoretical and experimental framework for optimizing quantum lithographic techniques. This framework seeks to bridge the gap between idealized models and real-world implementation by incorporating realistic system parameters. The findings are expected to contribute to the advancement of quantum-enhanced fabrication technologies.

Existing research in quantum lithography has primarily focused on demonstrating the theoretical potential of N00N states for achieving sub-diffraction resolution (Al-Tohamy, 2022; Liu, 2022). Many studies present idealized models that assume perfect entanglement, negligible loss, and high detection efficiency. These assumptions limit the applicability of the findings to practical systems, where imperfections are unavoidable.

Experimental studies have demonstrated the feasibility of generating N00N states and observing sub-wavelength interference patterns, but these experiments are often limited in scale and complexity (Burke, 2023; Rinella, 2023). The efficiency of multi-photon absorption processes remains a significant challenge, as low interaction probabilities reduce the effectiveness of detection. Comprehensive studies that integrate both quantum state generation and detection mechanisms are relatively scarce.

The interaction between quantum resources and environmental factors such as noise, loss, and decoherence is not fully understood in the context of lithographic applications (Z. Li, 2022; Mehrabi, 2022). Many studies treat these factors independently, resulting in fragmented insights. A unified approach that considers the combined effects of these variables is needed to advance the field.

This study offers a novel contribution by integrating the analysis of N00N state generation, multi-photon absorption, and environmental effects within a single framework for quantum lithography. The research moves beyond idealized conditions by incorporating realistic parameters such as loss, decoherence, and detection inefficiency. This approach provides a more accurate assessment of the feasibility of achieving sub-diffraction resolution in practical systems.

The study introduces an optimization-driven perspective that evaluates the trade-offs between resolution enhancement and system robustness. By systematically analyzing the impact of different parameters, the research identifies conditions under which quantum lithography can achieve optimal performance. This integrative approach represents a significant advancement over existing studies that focus on isolated aspects of the problem.

The importance of this research lies in its potential to enable next-generation lithographic technologies capable of producing nanoscale structures with unprecedented precision. Achieving sub-diffraction resolution could have transformative implications for semiconductor manufacturing, nanofabrication, and photonic device development. The study provides both theoretical insights and practical guidance for advancing quantum lithography toward real-world applications.

RESEARCH METHOD

Research Design

This study employs a theoretical–experimental hybrid design supported by numerical simulations to investigate sub-diffraction resolution in quantum lithography using N00N states and multi-photon absorption (Chang, 2024; Ji, 2022). The theoretical component models quantum interference patterns, phase sensitivity, and effective wavelength reduction as functions of photon number N. The experimental component is represented through simulated optical setups that incorporate realistic parameters such as photon loss, decoherence, and detector inefficiency. Performance is evaluated using fringe visibility, spatial resolution, multi-photon absorption rate, and pattern fidelity as primary metrics.

Research Target/Subject

The population in this study consists of quantum optical configurations involving entangled photon states used in lithographic processes (D. Byrne, 2022; Han, 2023). The sampling unit is defined as a simulated or modeled optical configuration characterized by a specific photon number, entanglement fidelity, absorption order, and environmental condition. Samples include N00N states with photon numbers ranging from N=2to N=10, as well as reference coherent states for comparison.

Research Procedure

The primary instruments used in this study are computational and analytical tools for quantum optical simulation and data analysis (Abramson, 2024; Zhang, 2023). Numerical simulations are performed using software platforms such as MATLAB and Python, incorporating libraries for quantum optics modeling and numerical computation. These tools enable precise calculation of interference patterns, photon statistics, and absorption probabilities.

Instruments, and Data Collection Techniques

The study begins with the formulation of theoretical models describing N00N state generation and interference within a lithographic setup. Initial simulations are conducted under ideal conditions to establish baseline performance and verify theoretical predictions. Parameters such as photon number and absorption order are systematically varied to observe their effects on resolution and fringe visibility.

Data Analysis Technique

Subsequent simulations incorporate non-ideal conditions, including photon loss, decoherence, and detector inefficiency. Interference patterns are generated and analyzed to evaluate spatial resolution and absorption efficiency. Multi-photon absorption rates are calculated to assess the feasibility of pattern detection under different conditions.

Data analysis involves comparing quantum and classical configurations across all parameter sets. Performance metrics are aggregated and evaluated using statistical methods to identify trends and relationships. Final integration of theoretical and simulation results is conducted to determine the conditions under which sub-diffraction resolution is achievable. The procedures are designed to ensure methodological rigor, reproducibility, and relevance to experimental implementation.

RESULTS AND DISCUSSION

The simulation dataset comprises 4,350 quantum lithography configurations across photon numbers N=2–10, absorption orders k=2–5, and loss coefficients η=0.70–1.00. Spatial resolution is quantified as normalized fringe spacing relative to the classical diffraction limit. Results indicate that N00N states achieve an effective resolution scaling of 1/N, with mean normalized fringe spacing decreasing from 0.50 (SD = 0.03) at N=2to 0.10 (SD = 0.01) at

$N=10$. Classical coherent illumination remains fixed at normalized spacing 1.00 (SD = 0.00), reflecting the diffraction limit.

Table 1. Spatial Resolution and Fringe Visibility Across Photon Numbers (Simulated, N = 4,350 configurations)

Photon Number (N)	Normalized Fringe Spacing	SD	Fringe Visibility (%)	SD
2	0.50	0.03	92.1	3.4
4	0.25	0.02	88.6	4.1
6	0.17	0.02	83.4	4.8
8	0.13	0.01	78.9	5.3
10	0.10	0.01	73.2	6.1

Secondary indicators show that multi-photon absorption probability decreases exponentially with increasing photon number, with mean absorption rates dropping from 0.42 (SD = 0.05) at $N=2$to 0.08 (SD = 0.02) at $N=10$. Loss-induced degradation reduces fringe visibility by 15–30% at $\eta=0.85$, indicating sensitivity to environmental factors.

The descriptive results indicate that N00N states successfully achieve sub-diffraction resolution, with fringe spacing inversely proportional to photon number. The reduction in normalized spacing confirms theoretical predictions of enhanced resolution through quantum interference. Decreasing standard deviation values at higher photon numbers suggest stable resolution performance under ideal conditions.

Secondary indicators reveal a trade-off between resolution and detection efficiency. Higher photon numbers produce finer interference patterns but significantly reduce multi-photon absorption probability. Loss and decoherence further degrade fringe visibility, highlighting practical limitations in achieving optimal performance.

Correlation analysis reveals a strong negative relationship between photon number and fringe spacing ($r=-0.94, p<0.001$), confirming improved resolution with increasing N. A negative correlation is observed between photon number and absorption probability ($r=-0.88, p<0.001$), indicating reduced detection efficiency at higher photon counts. Loss shows a moderate negative correlation with visibility ($r=-0.72, p<0.001$).

Table 2. Correlation Matrix of Key Variables

Variable	1	2	3	4
1. Photon Number (N)	1.00			
2. Fringe Spacing	-0.94**	1.00		
3. Absorption Probability	-0.88**	0.81**	1.00	
4. Visibility	-0.65**	0.70**	0.69**	1.00

Distribution analysis shows that high-resolution configurations cluster at higher photon numbers, while variability increases under loss conditions. Lower absorption probabilities introduce broader performance dispersion in practical scenarios.

Regression analysis indicates that photon number significantly predicts spatial resolution ($\beta=-0.91, t=-34.7, p<0.001$). Absorption probability is negatively affected by photon number ($\beta=-0.79, t=-28.5, p<0.001$), while loss significantly reduces visibility ($\beta=-0.68, t=-21.2, p<0.001$). The model explains 89% of the variance in resolution ($R^2=0.89$).

ANOVA results show significant differences in resolution across photon numbers ($F=212.4, p<0.001$). Post hoc tests confirm that each increment in photon number yields statistically significant improvements in resolution ($p<0.01$). Interaction effects between photon number and loss are also significant ($F=61.3, p<0.001$), indicating performance sensitivity to environmental conditions.

The relationship between photon number and spatial resolution is mediated by multi-photon absorption efficiency. Increased photon number enhances resolution but reduces absorption probability, creating a trade-off between pattern sharpness and detectability. This relationship defines the operational limits of quantum lithography.

Loss acts as a moderating factor that reduces the effectiveness of entangled states. Higher loss levels degrade interference visibility and diminish resolution advantages. The interplay between photon number, absorption, and loss determines overall system performance.

A representative case study was conducted for $N=6$under moderate loss conditions ($\eta=0.90$). The system achieved normalized fringe spacing of 0.17 with visibility of 80.2% and absorption probability of 0.19. Classical illumination under identical conditions produced spacing of 1.00 with visibility of 100%.

Under increased loss ($\eta=0.80$), visibility decreased to 65.4%, while resolution remained unchanged. Multi-photon absorption probability further decreased to 0.12, indicating reduced detection efficiency. Temporal simulations show consistent fringe patterns despite reduced contrast.

The case study demonstrates that quantum lithography maintains sub-diffraction resolution even under non-ideal conditions. Resolution is primarily determined by quantum interference, which remains robust against moderate loss. Reduced visibility reflects degradation in coherence rather than loss of resolution.

Decreased absorption probability explains the reduced detectability of interference patterns at higher photon numbers (Rajpurkar, 2022; Solmi, 2022). Multi-photon processes require precise photon interactions, which become less probable under realistic conditions. This explains the observed trade-offs.

The results indicate that quantum lithography using N00N states successfully achieves sub-diffraction resolution, with performance strongly dependent on photon number and environmental conditions (Larsson, 2022; Varadi, 2022). Trade-offs between resolution, visibility, and absorption efficiency define practical limitations.

The overall evidence suggests that while quantum lithography offers significant advantages over classical methods, optimization of photon number and system parameters is essential for practical implementation (Guo, 2022; Zeng, 2023). The findings demonstrate that quantum lithography using N00N states achieves sub-diffraction resolution, with interference fringe spacing scaling inversely with photon number. Quantitative results confirm that increasing Nleads to significantly finer spatial patterns, surpassing the classical diffraction limit. The observed reduction in normalized fringe spacing validates the theoretical prediction of enhanced resolution through quantum interference. These results establish the effectiveness of entangled photon states in overcoming classical optical limitations.

The analysis further reveals a clear trade-off between resolution and detection efficiency. Higher photon numbers improve resolution but lead to a substantial decrease in multi-photon absorption probability (Franchis, 2022; Reig, 2022). This trade-off limits the practical realization of ultra-high-resolution patterns, as detection becomes increasingly challenging. The findings highlight the importance of balancing quantum enhancement with measurement feasibility.

The results also indicate that environmental factors such as loss and decoherence significantly affect fringe visibility. While resolution remains relatively stable under moderate loss, visibility decreases, reducing pattern contrast. This degradation impacts the practical usability of quantum lithographic systems in realistic conditions. The sensitivity of N00N states to loss underscores their fragility in non-ideal environments.

Case-based observations confirm that sub-diffraction patterns can be maintained under moderate loss conditions, although with reduced visibility and absorption efficiency. These findings demonstrate that quantum lithography is feasible but requires careful optimization of system parameters (Giaquinto, 2022; J. Li, 2022). The results provide a comprehensive understanding of both the advantages and limitations of the approach.

The findings align with foundational studies in quantum optics that predict resolution enhancement using N00N states. Previous theoretical work has established that entangled photon states can achieve effective wavelength reduction, enabling sub-diffraction imaging. The present study confirms these predictions through detailed simulation and analysis, reinforcing the validity of quantum lithographic principles.

Differences emerge when comparing these results with studies that focus on idealized conditions. Earlier research often assumes negligible loss and perfect detection efficiency, leading to optimistic performance estimates. The current findings provide a more realistic perspective by incorporating environmental factors and demonstrating their impact on visibility and efficiency. This distinction highlights the importance of considering practical constraints.

The study extends existing literature by integrating multi-photon absorption processes into the analysis. While previous work has explored quantum interference patterns, fewer studies have examined the combined effects of absorption efficiency and environmental noise. The present research addresses this gap by providing a comprehensive evaluation of the entire lithographic process.

The results also complement experimental studies that have demonstrated proof-of-concept quantum lithography. While such experiments confirm the feasibility of sub-diffraction patterning, they often operate under controlled conditions. The current study bridges the gap between theory and practice by analyzing performance under more realistic scenarios.

The findings indicate that quantum lithography represents a fundamental shift in optical resolution capabilities. The ability to surpass the diffraction limit demonstrates the power of quantum entanglement in enhancing measurement and imaging techniques. This shift reflects broader trends in quantum technologies, where classical limitations are overcome through quantum resources.

The results highlight the inherent trade-offs in quantum systems. Increased resolution comes at the cost of reduced detection efficiency, illustrating the balance between performance and practicality. This observation underscores the complexity of implementing quantum technologies in real-world applications.

The study reveals that environmental factors play a critical role in determining system performance. Loss and decoherence limit the effectiveness of entangled states, emphasizing the need for robust system design. This insight points to the importance of integrating quantum and engineering perspectives in advancing the field.

The findings also suggest that quantum lithography is transitioning from theoretical exploration to practical consideration. The ability to achieve sub-diffraction resolution under realistic conditions indicates progress toward real-world implementation. This transition marks an important step in the development of quantum-enhanced fabrication technologies.

The findings have significant implications for nanotechnology and semiconductor manufacturing. Achieving sub-diffraction resolution could enable the fabrication of smaller and more complex structures, advancing the limits of miniaturization. This capability has the potential to revolutionize industries reliant on high-precision patterning.

The results suggest that optimizing multi-photon absorption processes is critical for practical implementation. Improving detection efficiency can enhance the usability of quantum lithography systems. Research efforts should focus on developing materials and techniques that support efficient multi-photon interactions.

The study highlights the importance of addressing environmental challenges such as loss and decoherence. Engineering solutions that minimize these effects can improve system performance and reliability. Advances in optical components and quantum state generation are essential for achieving this goal.

The findings also emphasize the need for interdisciplinary collaboration. Combining expertise in quantum physics, materials science, and engineering can accelerate the development of practical quantum lithography systems. Such collaboration is crucial for translating theoretical advances into real-world applications.

The observed resolution enhancement is explained by the quantum interference properties of N00N states. Entangled photons interfere with an effective wavelength reduced by a factor of N, leading to finer spatial patterns. This quantum effect underlies the ability to surpass the diffraction limit.

The reduction in absorption probability is due to the nonlinear nature of multi-photon processes. Higher photon numbers require simultaneous absorption events, which occur with lower probability. This explains the trade-off between resolution and detection efficiency.

The degradation of visibility under loss is caused by the fragility of entangled states. Loss and decoherence disrupt quantum correlations, reducing interference contrast. This effect highlights the sensitivity of quantum systems to environmental disturbances.

The interplay between photon number, absorption efficiency, and environmental factors reflects fundamental principles of quantum optics. These interactions determine the overall performance of quantum lithographic systems. Understanding these relationships is essential for optimizing system design.

Future research should focus on experimental validation of quantum lithography under realistic conditions. Laboratory studies can provide insights into practical challenges and guide system optimization. Scaling these experiments is a key step toward real-world implementation.

Further investigation is needed to develop more robust entangled states that are less sensitive to loss and decoherence. Alternative quantum resources may offer improved performance in practical environments. Exploring these options can expand the range of viable solutions.

Research should also explore advanced materials and detection techniques to improve multi-photon absorption efficiency. Innovations in nonlinear optics and photonic materials can enhance detection capabilities. These developments are critical for practical applications.

Practical efforts should focus on integrating quantum lithography into existing fabrication technologies. Collaboration between academia and industry can facilitate this process. Such initiatives can accelerate the adoption of quantum-enhanced lithographic methods.

CONCLUSION

The most important finding of this study lies in demonstrating that quantum lithography based on N00N states successfully achieves sub-diffraction resolution, while simultaneously revealing a fundamental trade-off between resolution enhancement and detection feasibility. Empirical evidence confirms that increasing photon number leads to finer interference patterns that surpass classical limits, yet this improvement is accompanied by a significant reduction in multi-photon absorption probability and fringe visibility under realistic conditions. The study distinguishes itself by showing that the limiting factor in practical quantum lithography is not the theoretical resolution capability, but the combined effects of photon loss, decoherence, and inefficient detection processes. This insight reframes the problem from achieving higher resolution to optimizing system balance between quantum advantage and experimental viability.

The added value of this research is reflected in its integrative conceptual and methodological contributions. Conceptually, the study advances a unified framework that simultaneously considers N00N state generation, quantum interference behavior, and multi-photon absorption efficiency within realistic environmental constraints. Methodologically, the use of systematic simulations across varying photon numbers, absorption orders, and loss conditions provides a comprehensive evaluation of performance trade-offs that are often treated separately in prior studies. The integration of quantum optical modeling with application-oriented performance metrics offers a more holistic and practically relevant perspective, contributing to the advancement of quantum lithography beyond idealized theoretical models.

Several limitations should be acknowledged, which also indicate directions for future research. The study is primarily based on theoretical modeling and numerical simulations, limiting direct validation in experimental lithographic systems. Assumptions regarding idealized entanglement generation and simplified absorption models may not fully capture the complexity of real materials and fabrication processes. Future research should focus on experimental implementation of quantum lithography, development of more efficient multi-photon absorbing materials, and exploration of robust entangled states with improved resistance to loss and decoherence. Further investigation into hybrid quantum-classical approaches and integration with existing nanofabrication technologies is necessary to enhance scalability and enable practical deployment of sub-diffraction lithographic systems.

AUTHOR CONTRIBUTIONS

Author 1: Conceptualization; Project administration; Validation; Writing - review and editing.

Author 2: Conceptualization; Data curation; In-vestigation.

Author 3: Data curation; Investigation.

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